# P-2-7 <br> Photoluminescence of Field-Effect Quantum Dot Arrays Based on a Be-Delta Doped Single Heterojunction 

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## 1. Introduction

Field-effect lateral quantum dot (QD) structures have been attracting interests [1]. One of the advantages of them is that the confinement potential is tunable and transition from 2 dimensional (D) to 0 D electron systems can be studied in single sample by changing the bias voltage.

A magneto-photoluminescence
(PL) measurement was reported previously for a sample based on a GaAs modulation-doped quantum well (MDQW) structure [2]. It was shown that the Fermi-edge singularity depends on the applied bias voltage. Because an optically created hole is mobile in a MDQW, both the motions of electrons and a hole are modulated by the bias voltage. This obscured direct identification of 0 D electron system in the PL spectra.

Field-effect lateral quantum dot structures based on a Be-delta doped single heterojunction (SHJ) are one of the candidates to overcome the above difficulty. The PL spectra of Be-delta doped SHJ due to the radiative recombination of electrons with a hole are known to directly reflect the electron density of states [3]. Because of the strong localization, a hole bound to an acceptor can recombine with any electrons with momentum $\mathbf{k}$ with nearly equal optical transition probabilities. Thus the PL spectrum gives a direct method to investigate the electron systems.

The purpose of the present paper is to show that the electron density of states can be in fact tunable from 2 D to 0 D by the bias voltage in the field-effect lateral QD structure by PL measurements.

## 2. Experiments

The sample studied was a molecular-beam epitaxy grown GaAs-AlGaAs Be-delta doped SHJ structure on a $n$-type GaAs substrate used as a backgate. The electron density was estimated to be $5.6 \times 10^{11} \mathrm{~cm}^{-2}$. A Ti/Au semi-transparent surface Schottky gate structures was fabricated with a square mesh of a period of 200 nm by the electron beam lithography. A sample with unpatterned surface Schottky gate structure was also studied for comparison. The sample was illuminated at 532 or 785 nm at the excitation power density of less than 2 $\mathrm{mW} / \mathrm{cm}^{2}$.

## 3. Results and Discussions

### 3.1 Unpatterned surface gate case

A sample with an unpatterned surface gate structure is studied before proceeding to a lateral QD structure. Figure 1 shows bias voltage dependent PL spectra depending on the applied bias voltage between the backgate and the unpatterned surface gate structure at 1.8 K illuminated at 532 nm . The band gap $\left(E_{g}\right)$ and the Fermi energy $\left(E_{F}\right)$ are located at around 1.478 and 1.495 eV , respectively, at $V_{B}=0 \mathrm{~V}$. The electrons are slightly depeleted due to the metal deposition on the surface. The PL intensity between $E_{g}$ and $E_{F}$ are seen to be nearly flat, reflecting the 2 D density of states. $E_{g}$ and $E_{F}$ shift to higher and lower energies, respectively, with decrease in $V_{B}$. This shows that the electron density below the unpatterned surface gate structure decreases with decrease in $V_{B}$. At $V_{B} \leq-1.8 \mathrm{~V}$, the PL from the electron system becomes very weak, showing that the electrons below the surface gate structure are


Fig. 1 Bias voltage dependent PL spectra of a sample with an unpatterned surface Schottky gate structure at 1.7 K . The bias voltage are varied as $0,-0.1,-0.2,-0.3,-0.4,-0.5,-0.6$, $-0.7,-0.8,-0.9,-1.0,-1.2,-1.4,-1.6,-1.8$, and -2.0 V . Zero points of the $y$ axis are shifted.
completely depleted.

### 3.2 Square mesh surface gate case

Contrasting with the PL of the unpatterned sample, the bias voltage dependent PL spectra of a sample with a square mesh of a period of 200 nm as shown in Fig. 2 show two distinct behaviors. First, the band gap shown by the arrow is constant between $V_{B}=0$ and -2.0 V . This indicates that the electron density is constant in the area contributing to the observed PL. Second, the PL lineshape changes with $V_{B}$. The PL intensity increases almost linearly with energy between $E_{g}$ and $E_{F}$ at $V_{B}=-2.0 \mathrm{~V}$, which contrasts with the flat PL intensity between $E_{g}$ and $E_{F}$ at $V_{B}=0 \mathrm{~V}$. This almost linear increase of the PL intensity with the energy shows that the density of states of the electrons in the sample at $V_{B}=-2.0 \mathrm{~V}$ is approximately described by that of the 2 D harmonic oscillator. In the 2 D harmonic oscillator, the degeneracy of the states increases linearly with the increase in the principal quantum number.

The above result shows that confined electron states are created at $V_{B}=-2.0 \mathrm{~V}$ with nearly the same aerial electron density in the center of the QD as that in 2D at $V_{B}=0 \mathrm{~V}$.


Fig. 2 Bias voltage dependent PL spectra of a sample with a square mesh of a period of 200 nm Schottky gate structure at 3.3 K . The bias voltage are varied as (i) 0 , (ii) -0.5 , (iii) -0.8 , (iv) -1.0 , (v) -1.5 , (vi) -1.8 , and (vii) -2.0 V . Zero points of the y axis are shifted.

## 4. Conclusions

We have shown that the bias voltage dependent PL spectra of the Be-delta-doped sample indicate a 0 D density of states of electrons at negative bias voltages. This shows that quantum dots are formed in our field-induced quantum dot array structure.

## References

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